

Evaluating the Topological Surface Properties of Cu/Cr Thin Films Using 3D Atomic Force Microscopy Topographical Maps

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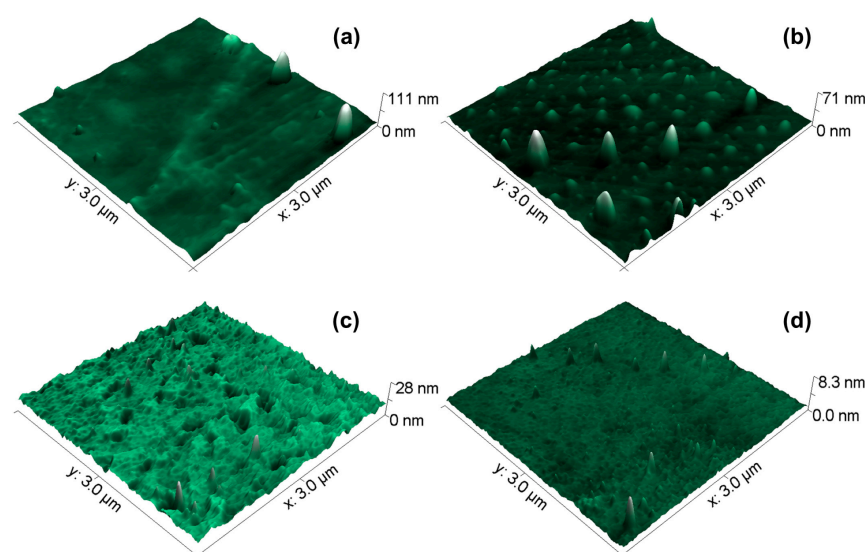


Figure S1. 3D AFM topographical maps of (a) BK7, (b) Glass, (c) ITO, and (d) Si substrates.

Table S1. Roughness of BK7, Si, and Glass substrates, according to ISO 25178-2:2012. The average results were expressed as mean values and standard deviation.

Parameter	Unit	Bk7	Glass	ITO	Si
Sq	[nm]	6.77 ± 1.36	6.82 ± 2.87	1.89 ± 0.05	0.85 ± 0.45